ABSTRACT

A method of manufacturing a semiconductor device includes designing a semiconductor device layout using a design rule manual (DRM), in which design rules are recorded, and performing failure evaluation of a failure including at least one gate structure failure of a semiconductor device manufactured using the designed semiconductor device layout. The method further includes updating the DRM by updating the design rules recorded in the DRM, based on a result of the failure evaluation, redesigning the semiconductor device layout using the updated DRM, and manufacturing the semiconductor device using the redesigned semiconductor device layout.

FIG. 3